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(12) **United States Design Patent** (10) **Patent No.:** **US D1,017,561 S**
Shimada (45) **Date of Patent:** **** Mar. 12, 2024**

(54) **NOZZLE HOLDER OF SUBSTRATE PROCESSING APPARATUS**

(71) Applicant: **KOKUSAI ELECTRIC CORPORATION**, Tokyo (JP)

(72) Inventor: **Hironori Shimada**, Toyama (JP)

(73) Assignee: **KOKUSAI ELECTRIC CORPORATION**, Tokyo (JP)

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(51) **LOC (14) Cl.** **13-03**

(52) **U.S. Cl.**
USPC **D13/182**

(58) **Field of Classification Search**
USPC D11/79, 95, 96, 222; D13/103, 104, 110, D13/119, 120, 121, 123, 133, 158, 162, D13/182, 184, 199; D19/40; D15/144.1; D8/2, 382, 399; D9/434; D7/591; D23/213, 227, 259, 324, 325, 354, 364
CPC B05B 15/622; B05B 15/65; B05B 1/00; B05B 1/02; B05B 1/04; B05B 1/05; B05B 5/00; B05B 5/002; B05B 5/025; B05B 5/0255; B05B 5/03; B05B 5/032; B24C 5/04; H01L 21/205; H01L 21/0228; H01M 10/613; H01M 10/625; H01M 50/209; H01M 50/262; H01M 50/502; H01M 50/503; H01M 50/507; H01M 50/553

See application file for complete search history.

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Primary Examiner — Shawn T Gingrich

Assistant Examiner — Caleb M Baker

(74) *Attorney, Agent, or Firm* — FITCH, EVEN, TABIN & FLANNERY, LLP

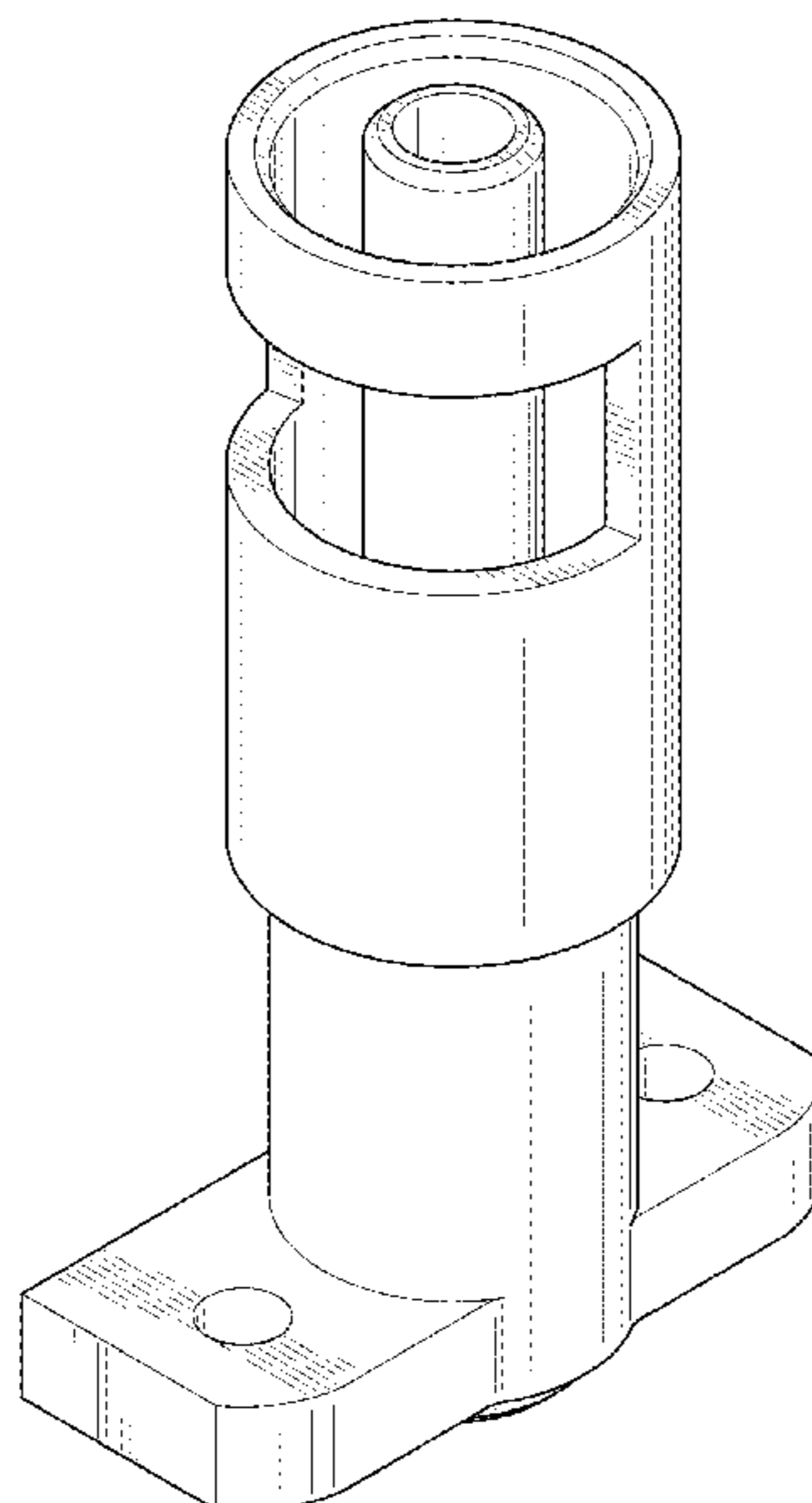
(57) **CLAIM**

The ornamental design for a nozzle holder of substrate processing apparatus, as shown and described.

DESCRIPTION

FIG. 1 is a front, top and right side perspective view of a nozzle holder of substrate processing apparatus showing our new design;
FIG. 2 is a front elevational view thereof;
FIG. 3 is a rear elevational view thereof;
FIG. 4 is a right side elevational view thereof;
FIG. 5 is a left side elevational view thereof;
FIG. 6 is a top plan view thereof;
FIG. 7 is a bottom plan view thereof; and,
FIG. 8 is a cross sectional view taken along line 8-8 in FIG. 2.

1 Claim, 5 Drawing Sheets



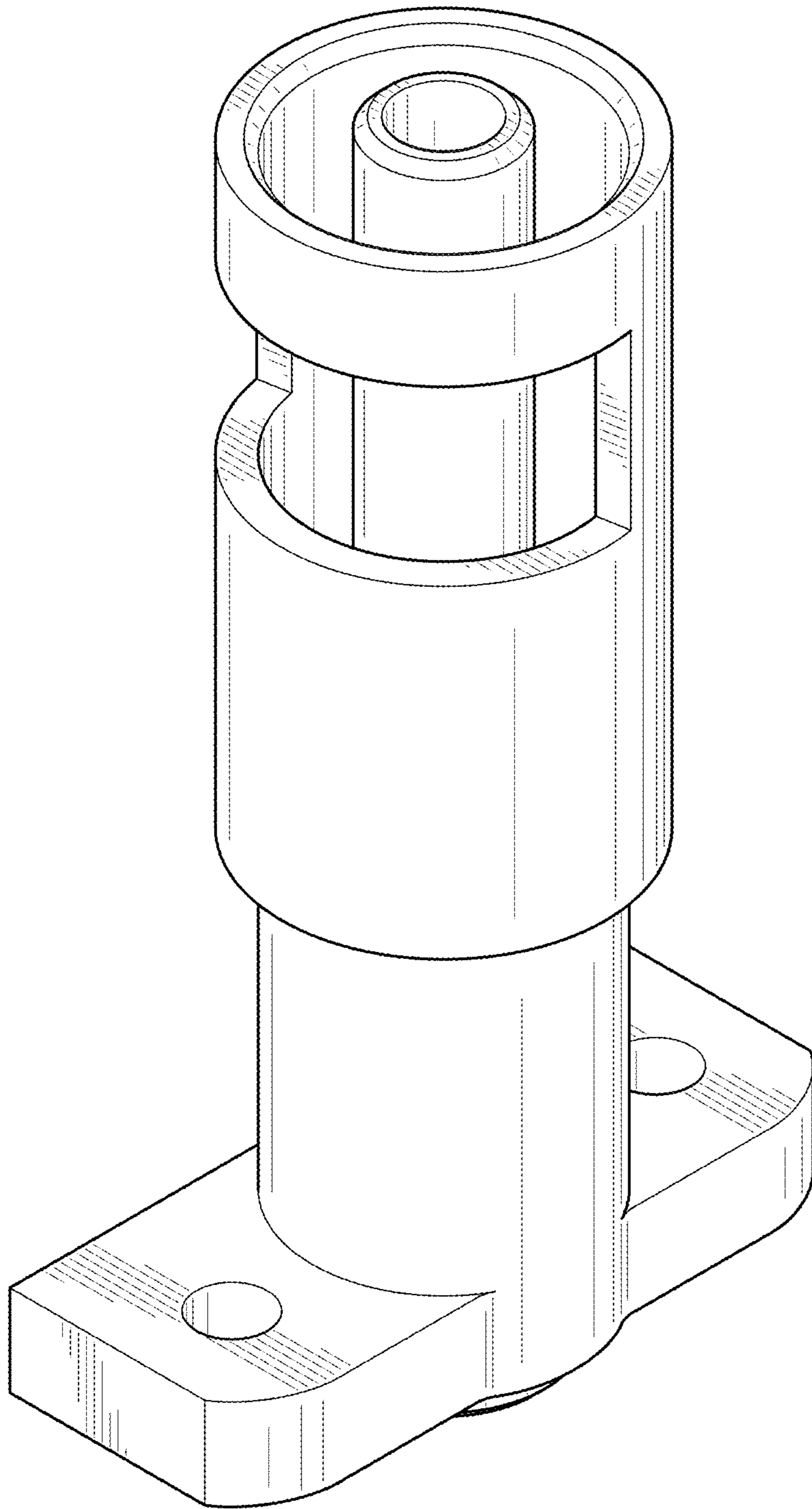


FIG. 1

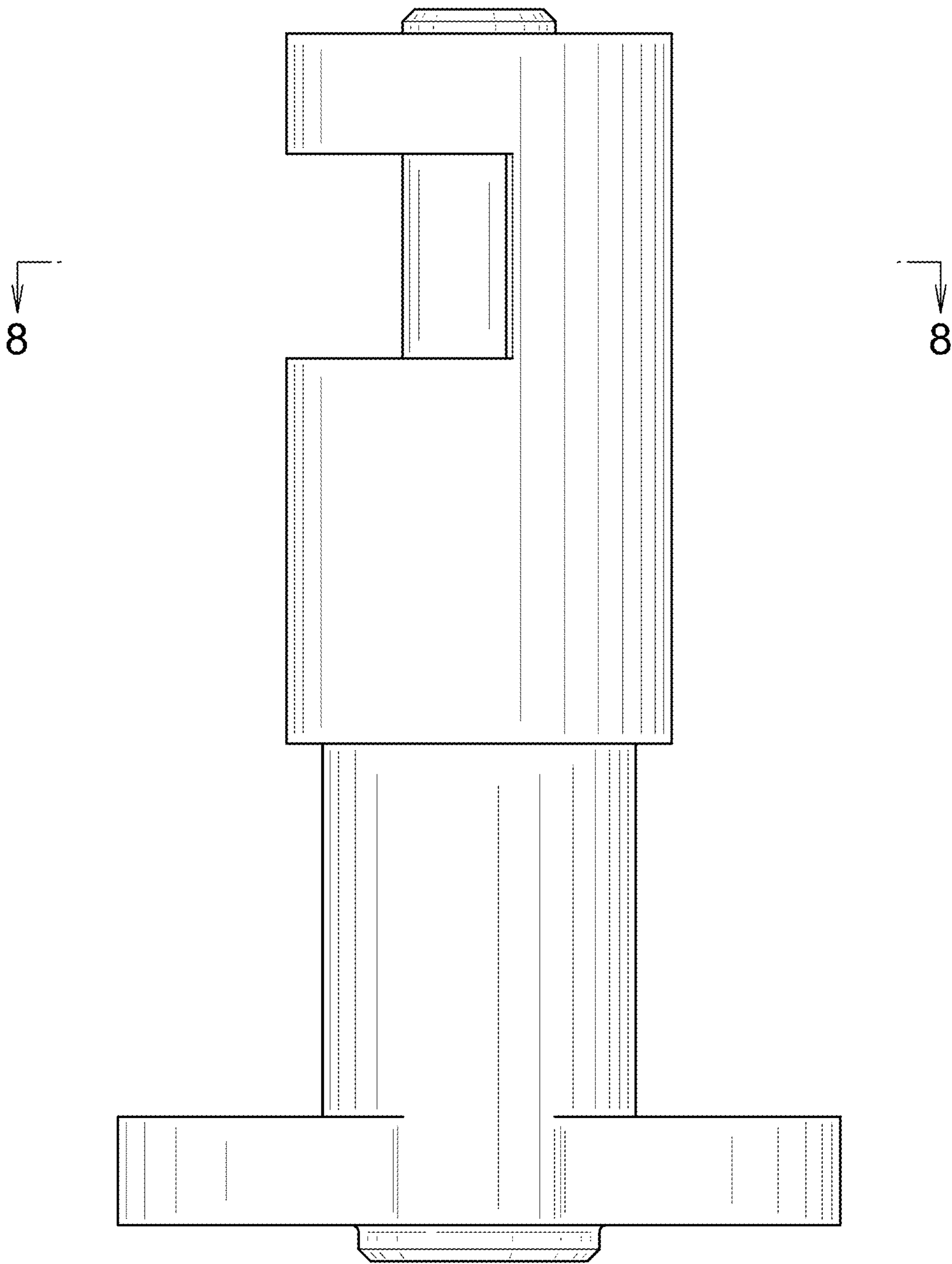


FIG. 2

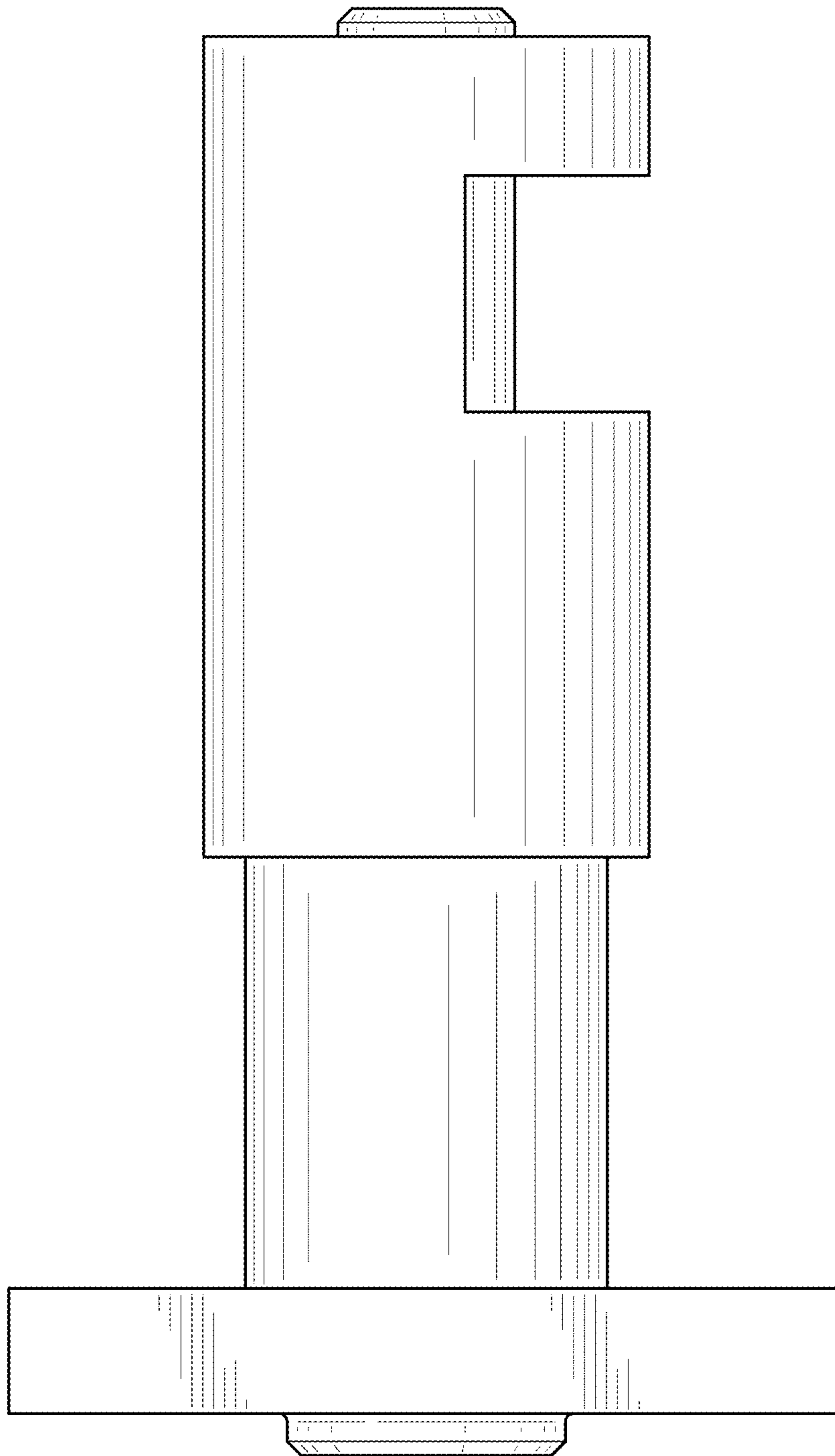


FIG. 3

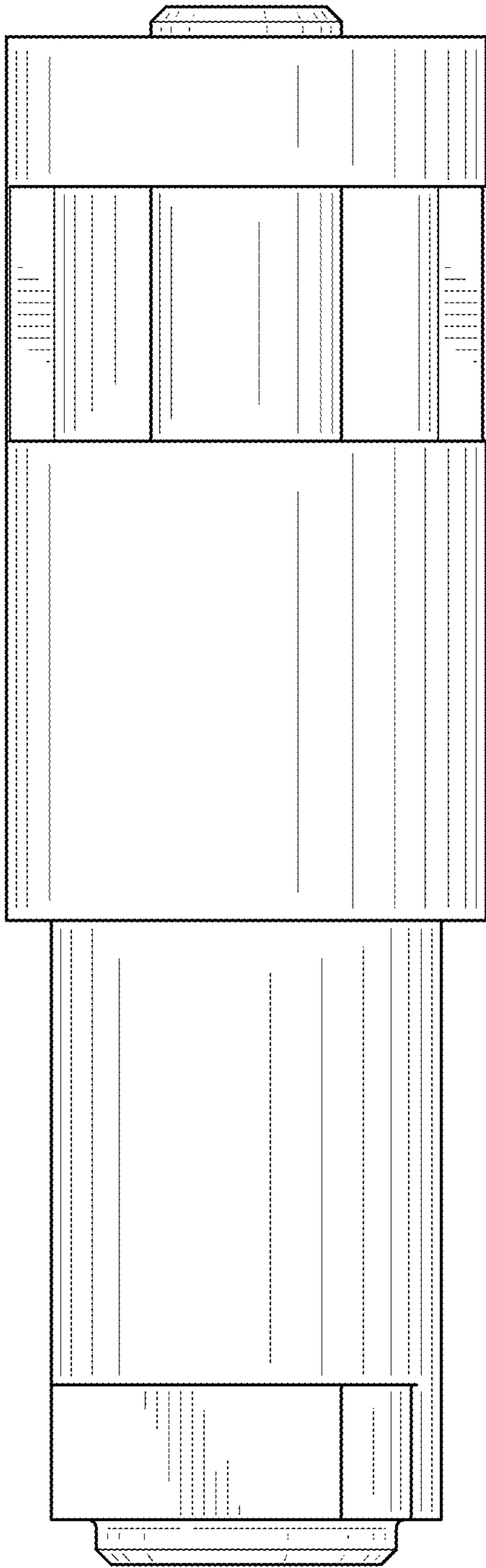


FIG. 4

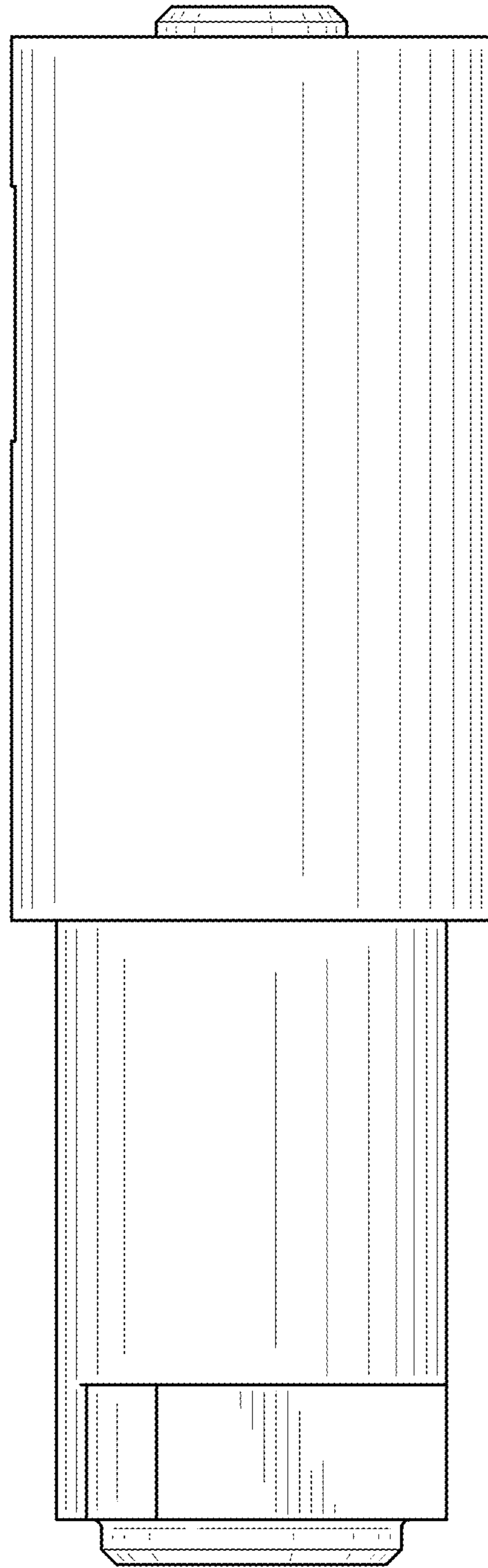


FIG. 5

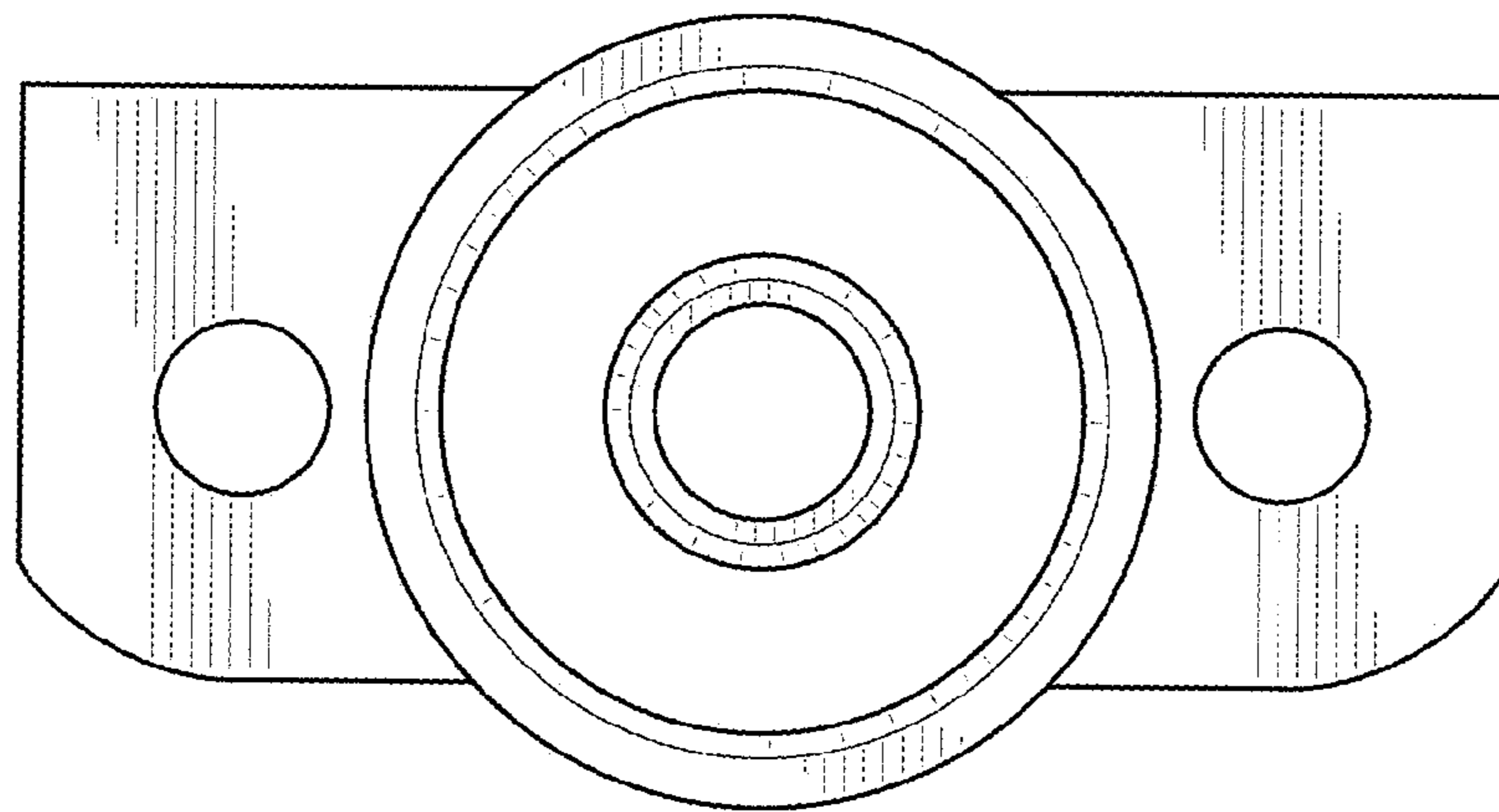


FIG. 6

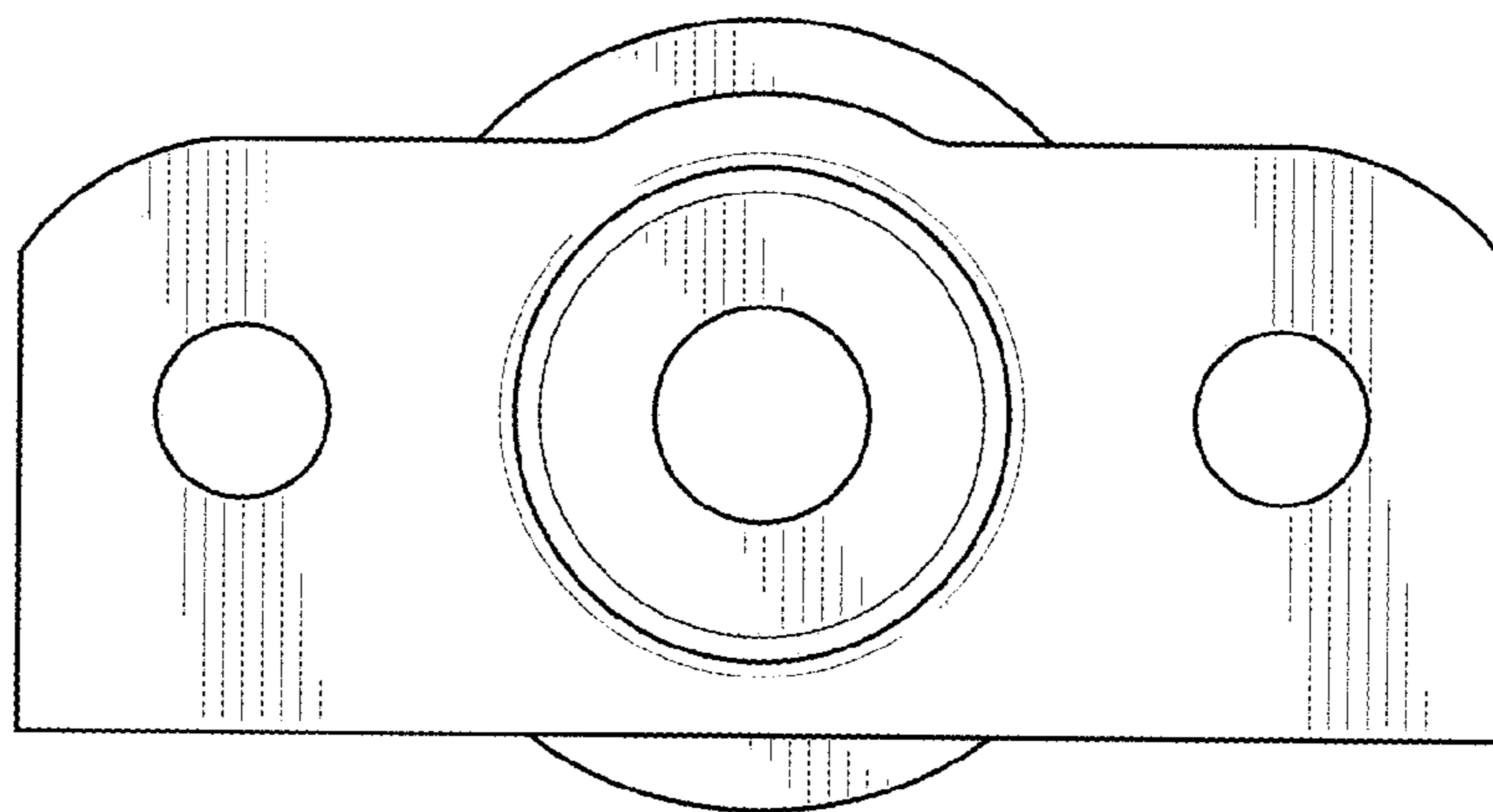


FIG. 7

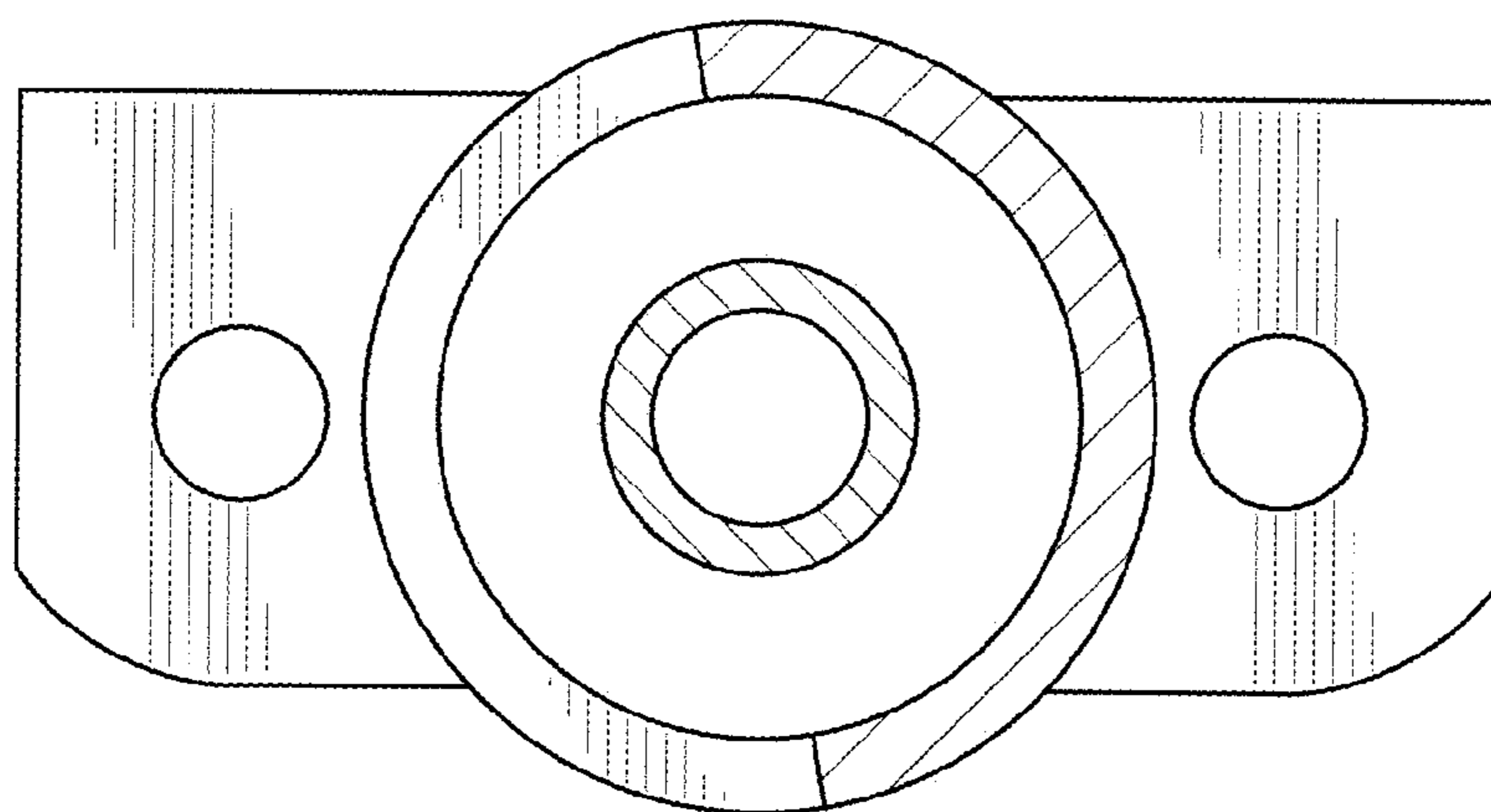


FIG. 8